Supporting Information

Facile synthesis of Ni-coated Ni₂P for supercapacitor applications

Yi Lu,^a Ji-kang Liu,^a Xia-yuan Liu,^a Sen Huang,^a Ting-qiang Wang,^a Xiu-li Wang,^a Chang-dong Gu,^a

Jiang-ping Tu, $*^a$ and Scott X. Mao^b

^a State Key Laboratory of Silicon Materials, Key Laboratory of Advanced Materials and Applications for Batteries of Zhejiang Provence and Department of Materials Science and Engineering, Zhejiang University, Hangzhou 310027, China

^b Department of Mechanical Engineering and Materials Science, University of Pittsburgh, Pittsburgh, Pennsylvania 15261, USA

*Corresponding author. E-mail: tujp@zju.edu.cn; tujplab@zju.edu.cn (Jiang-ping Tu)



Fig. S1 XRD patterns of Ni-coated nickel phosphides synthesized by different electroless plating times.



Fig. S2 SEM images of Ni-coated nickel phosphides synthesized by different electroless plating times: (a) 20 min; (b) 30 min; (c) 5 min.



Fig. S3 (a) XRD pattern of the annealed Ni-coated nickel phosphides at 500 °C for 1 h under flowing argon; (b) FTIR spectra of Ni-coated nickel phosphides before annealing.



Fig. S4 First three CV profiles of the Ni₂P/Ni composite obtained by 10 min of electroless plating time in the potential region of 0–0.7 V at a scan rate of 50 mV s⁻¹.











Fig. S5 (a) Galvanostatic discharge curves and (b) discharge specific capacitance of the Ni-coated Ni₂P synthesized by electroless plating for 20 min; galvanostatic discharge curves of the Ni-coated Ni₂P synthesized by electroless plating for (c) 30 min; (d) 5 min; (e) discharge specific capacitance of the Ni-coated Ni₂P synthesized by electroless plating for 5 min.